Novel Photolabile Protecting Group for Carbonyl Compounds

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Overview

- Background & History
- Synthesis
- Protection Cycle
- Substrate Selectivity
- Evidence for Proposed Mechanism
- Stability
- Conclusion

- The value of protecting groups in synthesis is difficult to overstate
- One of the major difficulties lies in their susceptibilities to reaction conditions and in differentiating similar moieties that are protected
- One solution to this is to design a protecting group that makes use of uncommon reaction conditions